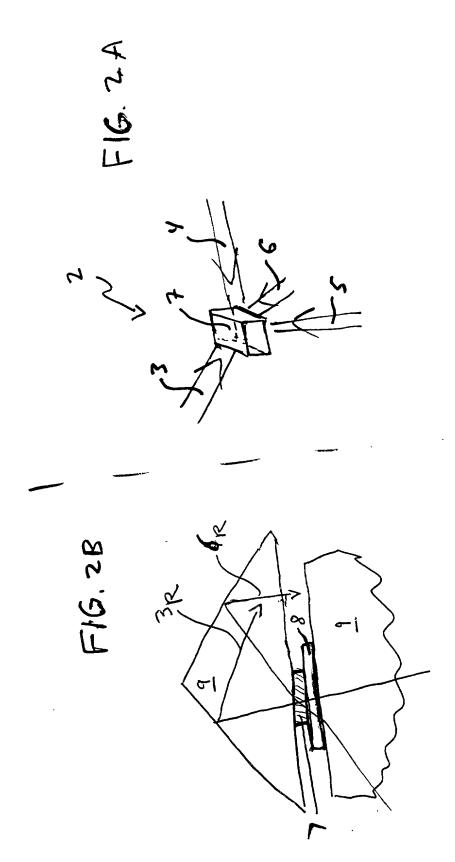
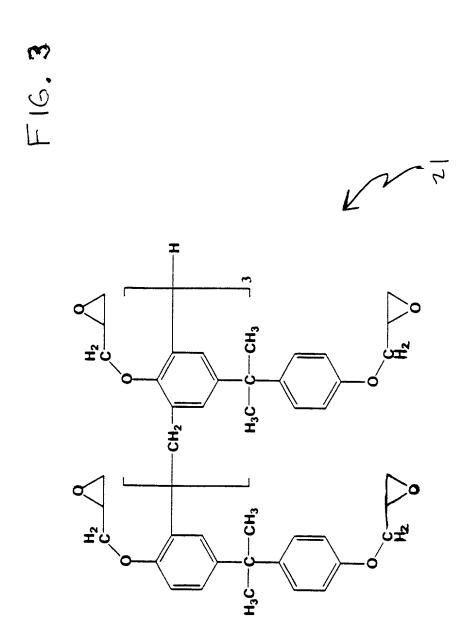
Provide photo-sensitive medium
Liz
conditions that inhibit refractive is pattern under
conditions that inhibit refractive index changes
I hoex changes
L14
Heat the exposed medium to favorize refractive index changing reactions
refractive indended medium to favorize
moex changing reactions
-16
wash the cured medium to remove either reacted or unrouted
either reacted or unreacted portions of the medium
Lie si the medium
/ 8
Dry the washed medium under conditions that limit internal stresses
conditions that limit internal structure
C20
10
F16.1



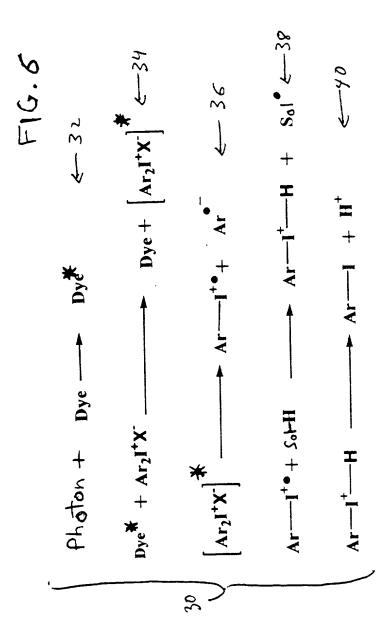


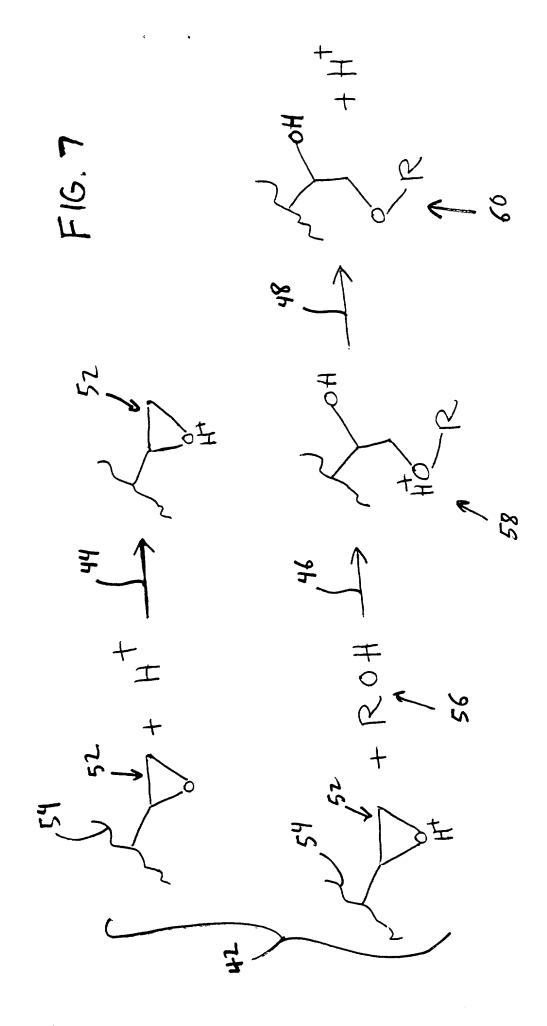
F16.4A

F16.48

F16.4C

F16.5A





Provide Photo-sensitive medium
12
Expose the medium to an intensity pattern
under conditions that inhibit refractive index changes
14
Segnentially expose a selected set
Segnentially expose a selected set of points and/or lines with a focal
region of a converging light beam
72
Heat the exposed medium to
favorize polymerization of oligoners therein
C16
√
wash the cured medium to remove
unpolymerized oligomers
C18
Dry the washed medium under conditions that limit internal stresses
2
70 F16. 8

Form a 3D polymer crystalline templa	te
. L82	-
Fill holes in the template with a high refractive index filler material	h
84	
Burn or etch away the polymer cr stalline template from the block	y-
7	
. 80° F1G. 9	

